

Larissa Juschkin

List of Publications by Year in descending order

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75
papers

609
citations

623734

14
h-index

713466

21
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79
all docs

79
docs citations

79
times ranked

443
citing authors

#	ARTICLE	IF	CITATIONS
1	Fundamentals and limits for the EUV emission of pinch plasma sources for EUV lithography. Journal Physics D: Applied Physics, 2004, 37, 3213-3224.	2.8	68
2	Optimization of a gas discharge plasma source for extreme ultraviolet interference lithography at a wavelength of 11 nm. Journal of Applied Physics, 2009, 106, .	2.5	38
3	Broadband transmission masks, gratings and filters for extreme ultraviolet and soft X-ray lithography. Thin Solid Films, 2012, 520, 5080-5085.	1.8	30
4	Scalability limits of Talbot lithography with plasma-based extreme ultraviolet sources. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2013, 12, 033002.	0.9	29
5	EUV emission from Kr and Xe capillary discharge plasmas. Journal Physics D: Applied Physics, 2002, 35, 219-227.	2.8	28
6	Ptychographic imaging with a compact gas discharge plasma extreme ultraviolet light source. Optics Letters, 2015, 40, 5574.	3.3	24
7	Table-top reflectometer in the extreme ultraviolet for surface sensitive analysis. Applied Physics Letters, 2009, 94, .	3.3	21
8	EUV microscopy for defect inspection by dark-field mapping and zone plate zooming. Journal of Physics: Conference Series, 2009, 186, 012030.	0.4	21
9	Achromatic Talbot lithography with partially coherent extreme ultraviolet radiation: process window analysis. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2016, 15, 043502.	0.9	19
10	<title>Comparison of different source concepts for EUVL</title> . , 2001, 4343, 215.		18
11	Laser triggered Z-pinch broadband extreme ultraviolet source for metrology. Applied Physics Letters, 2013, 102, 203504.	3.3	18
12	X-ray lasing as a result of an induced instability in an ablative capillary discharge. Journal Physics D: Applied Physics, 2001, 34, 336-339.	2.8	17
13	Diffraction-assisted extreme ultraviolet proximity lithography for fabrication of nanophotonic arrays. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2013, 31, 021602.	1.2	15
14	Generation of circularly polarized radiation from a compact plasma-based extreme ultraviolet light source for tabletop X-ray magnetic circular dichroism studies. Review of Scientific Instruments, 2014, 85, 103110.	1.3	15
15	Fractional Talbot lithography with extreme ultraviolet light. Optics Letters, 2014, 39, 6969.	3.3	14
16	Laser-assisted vacuum arc extreme ultraviolet source: a comparison of picosecond and nanosecond laser triggering. Journal Physics D: Applied Physics, 2016, 49, 225201.	2.8	13
17	Pinch Plasma Radiation Sources for the Extreme Ultraviolet. Contributions To Plasma Physics, 2001, 41, 589-597.	1.1	12
18	A phase retrieval algorithm based on three-dimensionally translated diffraction patterns. Europhysics Letters, 2015, 111, 64002.	2.0	11

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19	Quantitative characterization of absorber and phase defects on EUV reticles using coherent diffraction imaging. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2020, 19, 1.	0.9	11
20	Multi-angle spectroscopic extreme ultraviolet reflectometry for analysis of thin films and interfaces. Physica Status Solidi C: Current Topics in Solid State Physics, 2015, 12, 318-322.	0.8	9
21	Extreme ultraviolet proximity lithography for fast, flexible and parallel fabrication of infrared antennas. Optics Express, 2015, 23, 25487.	3.4	9
22	Status of EUV-lamp development and demonstration of applications. , 2004, 5374, 943.		8
23	Cross characterization of ultrathin interlayers in HfO ₂ high-k stacks by angle resolved x-ray photoelectron spectroscopy, medium energy ion scattering, and grazing incidence extreme ultraviolet reflectometry. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, 041506.	2.1	8
24	Compact extreme ultraviolet source for laboratory-based photoemission spectromicroscopy. Applied Physics Letters, 2016, 108, .	3.3	8
25	A capillary discharge as a pseudo-Planck radiator in the vacuum ultraviolet. Plasma Sources Science and Technology, 1999, 8, 370-375.	3.1	7
26	Metrology tools for EUV-source characterization and optimization. , 2004, , .		7
27	Optical properties of 2D fractional Talbot patterns under coherent EUV illumination. Journal Physics D: Applied Physics, 2015, 48, 375101.	2.8	7
28	Restorative Self-Image of Rough-Line Grids: Application to Coherent EUV Talbot Lithography. IEEE Photonics Journal, 2016, 8, 1-9.	2.0	7
29	Freeform lens collimating spectrum-folded Hadamard transform near-infrared spectrometer. Optics Communications, 2016, 380, 161-167.	2.1	7
30	Metrology tools for EUVL-source characterization and optimization. , 2003, , .		6
31	High-throughput EUV reflectometer for EUV mask blanks. , 2004, , .		6
32	Interferometric broadband Fourier spectroscopy with a partially coherent gas-discharge extreme ultraviolet light source. Optics Letters, 2015, 40, 2818.	3.3	6
33	Lloyd's mirror interference lithography with EUV radiation from a high-harmonic source. Applied Physics Express, 2016, 9, 076701.	2.4	6
34	Defect inspection with an EUV microscope. , 2010, , .		5
35	Structural properties of templated Ge quantum dot arrays: impact of growth and pre-pattern parameters. Nanotechnology, 2018, 29, 275601.	2.6	5
36	Fast and easy fabrication methodology of Fresnel zone plates for the extreme ultraviolet and soft x-ray regions. Applied Optics, 2019, 58, 1057.	1.8	5

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37	Line image sensors for spectroscopic applications in the extreme ultraviolet. Measurement Science and Technology, 2009, 20, 105201.	2.6	4
38	Two magnification steps EUV microscopy with a Schwarzschild objective and an adapted zone plate lens. , 2009, , .		4
39	Analysis of buried interfaces in multilayer mirrors using grazing incidence extreme ultraviolet reflectometry near resonance edges. Applied Optics, 2015, 54, 10351.	2.1	4
40	Update on the EUVL mask blank activity at Schott Lithotec. , 2003, , .		3
41	EUV Dark-Field Microscopy for Defect Inspection. AIP Conference Proceedings, 2011, , .	0.4	3
42	Analysis of distinct scattering of extreme ultraviolet phase and amplitude multilayer defects with an actinic dark-field microscope. , 2015, , .		3
43	Enabling laboratory EUV research with a compact exposure tool. Proceedings of SPIE, 2016, , .	0.8	3
44	Single Exposure Imaging of Talbot Carpets and Resolution Characterization of Detectors for Micro- and Nano- Patterns. Journal of the Optical Society of Korea, 2016, 20, 245-250.	0.6	3
45	EUV-LET 2.0: a compact exposure tool for industrial research at a wavelength of 13.5nm. , 2019, , .		3
46	Computational proximity lithography with extreme ultraviolet radiation. Optics Express, 2020, 28, 27000.	3.4	3
47	On space charge effects in laboratory-based photoemission electron microscopy using compact gas discharge extreme ultraviolet sources. New Journal of Physics, 2020, 22, 103019.	2.9	3
48	High speed imaging of Z-pinch gas discharge in extreme ultraviolet and model-based three-dimensional reconstruction of emitting volume. Review of Scientific Instruments, 2022, 93, 013503.	1.3	3
49	Innovative approaches to surface sensitive analysis techniques on the basis of plasma-based off-synchrotron XUV/EUV light sources. , 2008, , .		2
50	XUV metrology: surface analysis with extreme ultraviolet radiation. Proceedings of SPIE, 2009, , .	0.8	2
51	EUV actinic mask blank defect inspection: results and status of concept realization. Proceedings of SPIE, 2011, , .	0.8	2
52	Tabletop coherent diffraction imaging with a discharge plasma EUV source. , 2013, , .		2
53	Irradiation of low energy ions damage analysis on multilayers. Proceedings of SPIE, 2015, , .	0.8	2
54	Deposition and characterization of B4C/CeO2 multilayers at 6.x nm extreme ultraviolet wavelengths. Journal of Applied Physics, 2016, 119, .	2.5	2

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55	Spatially Resolved Spectroscopic Extreme Ultraviolet Reflectometry for Laboratory Applications. Journal of Nanoscience and Nanotechnology, 2019, 19, 562-567.	0.9	2
56	Extreme ultraviolet free-standing transmittance filters for high brilliance sources, based on Nb/Zr and Zr/Nb thin films on Si3N4 membranes: Design, fabrication, optical and structural characterization. Thin Solid Films, 2020, 695, 137739.	1.8	2
57	Optimized phase-shifting masks for high-resolution resist patterning by interference lithography. , 2017, , .		2
58	High speed reflectometer for EUV mask-blanks. , 2005, 5835, 252.		1
59	High speed reflectometer for EUV mask-blanks. , 2005, , .		1
60	Contributions to EUV mask metrology infrastructure. , 2010, , .		1
61	Spectral Sharpening Algorithm for a Polychromatic Reflectometer in the Extreme Ultraviolet. Applied Spectroscopy, 2010, 64, 401-408.	2.2	1
62	Actinic EUV-mask metrology: tools, concepts, components. , 2011, , .		1
63	Performance benchmark of a gateable microchannel plate detector for extreme ultraviolet radiation with high temporal resolution. , 2011, , .		1
64	Imaging with plasma based extreme ultraviolet sources. Proceedings of SPIE, 2012, , .	0.8	1
65	Employing partially coherent, compact gas-discharge sources for coherent diffractive imaging with extreme ultraviolet light. , 2015, , .		1
66	Ptychographic imaging with partially coherent plasma EUV sources. Advanced Optical Technologies, 2017, 6, 459-466.	1.7	1
67	Optical and structural characterization of orthorhombic LaLuO3 using extreme ultraviolet reflectometry. Thin Solid Films, 2019, 680, 94-101.	1.8	1
68	A scanning reflection X-ray microscope for magnetic imaging in the EUV range. Journal of Synchrotron Radiation, 2019, 26, 2040-2049.	2.4	1
69	Lensless Proximity EUV Lithography with a Xenon Gas Discharge Plasma Radiation. Springer Proceedings in Physics, 2016, , 313-319.	0.2	1
70	Investigation of X-ray lasing in a capillary discharge. European Physical Journal Special Topics, 2001, 11, Pr2-103-Pr2-106.	0.2	1
71	Holographic masks for computational proximity lithography with EUV radiation. , 2018, , .		1
72	Time resolved EUV pump-probe microscopy of fs-LASER induced nanostructure formation. , 2011, , .		0

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73	Quantum Efficiency Determination of a Novel CMOS Design for Fast Imaging Applications in the Extreme Ultraviolet. IEEE Transactions on Electron Devices, 2012, 59, 846-849.	3.0	0
74	Optical and structural characterization of CeO ₂ /B ₄ C multilayers near boron K-edge energy. , 2015, , .		0
75	Coherent Diffractive Imaging with a Laboratory-Scale, Gas-Discharge Plasma Extreme Ultraviolet Light Source. Springer Proceedings in Physics, 2016, , 275-280.	0.2	0